

ACTION: Notice of Intent to Grant a Patent License.

SUMMARY: NASA hereby gives notice of intent to grant CYTEC Engineered Materials, Inc., 1300 Revolution Street, Havre de Grace, Maryland 21078, an exclusive license to practice the invention protected by the U.S. Patent Application Number, 08/209/512 entitled "PHENYLETHYNYL TERMINATED IMIDE OLIGOMERS," which was filed on March 3, 1994, by the United States of America as represented by the Administrator of the National Aeronautics and Space Administration.

NASA hereby gives notice of intent to grant CYTEC Engineered Materials, Inc., 1300 Revolution Street, Havre de Grace, Maryland, 21078, a partially exclusive license to practice the invention protected by the U.S. Patent Application Number, 08/330,773 entitled "IMIDE OLIGOMERS ENDCAPPED WITH PHENYLETHYNYL PHTHALIC ANHYDRIDES AND POLYMERS THEREFROM," which was filed on October 28, 1994, by the United States of America as represented by the Administrator of the National Aeronautics and Space Administration.

The exclusive license will contain appropriate terms and conditions to be negotiated in accordance with NASA Patent Licensing Regulations (14 CFR part 1245). NASA will negotiate the final terms and conditions and grant the license unless, within 60 days of the date of this notice, the Director of Patent Licensing receives written objections to the grant, together with supporting documentation. The Director of Licensing will review all written responses to the notice and then recommend to the Associate General Counsel (Intellectual Property) whether to grant the license.

DATES: Comments to the Notice must be received by March 31, 1995.

ADDRESSES: National Aeronautics and Space Administration, Code GP, Washington, DC 20546.

FOR FURTHER INFORMATION CONTACT: Mr. Harry Lupuloff, NASA, Director of Patent Licensing, (202) 358-2041.

Dated: January 20, 1995.

Edward A. Frankle,
General Counsel.

[FR Doc. 95-2223 Filed 1-27-95; 8:45 am]

BILLING CODE 7510-01-M

[Notice 95-012]

Intent To Grant an Exclusive Patent License

AGENCY: National Aeronautics and Space Administration.

ACTION: Notice of Intent to Grant a Patent License.

SUMMARY: NASA hereby gives notice of intent to grant Imitec, Inc., of Schenectady, New York, 12301, a partially exclusive license to practice the invention protected by the U.S. Patent Application Number, 08/299,172 entitled, "COPOLYIMIDES PREPARED FROM ODP, BTDA AND 3,4'-ODA," which was filed on August 31, 1994, by the United States of America as represented by the Administrator of the National Aeronautics and Space Administration.

NASA hereby gives notice of intent to grant Imitec, Inc., of Schenectady, New York, 12301, a partially exclusive license to practice the invention protected by the U.S. Patent Application Number, 08/299,384, entitled "SOLVENT RESISTANT COPOLYIMIDE," which was filed on September 1, 1994, by the United States of America as represented by the Administrator of the National Aeronautics and Space Administration.

NASA hereby gives notice of intent to grant Imitec, Inc., of Schenectady, New York, 12301, a partially exclusive license to practice the invention protected by the U.S. Patent Application Number, 08/299,385, entitled "DIRECT PROCESS FOR PREPARING SEMICRYSTALLINE POLYIMIDES," which was filed on September 1, 1994, by the United States of America as represented by the Administrator of the National Aeronautics and Space Administration.

The partially exclusive license will contain appropriate terms and conditions to be negotiated in accordance with NASA Patent Licensing Regulations (14 CFR part 1245). NASA will negotiate the final terms and conditions and grant the license unless, within 60 days of the date of this notice, the Director of Patent Licensing receives written objections to the grant, together with supporting documentation. The Director of Patent Licensing will review all written responses to the notice and then recommend to the Associate General Counsel (Intellectual Property) whether to grant the license.

DATES: Comments to the notice must be received by March 31, 1995.

ADDRESSES: National Aeronautics and Space Administration, Code GP, Washington, DC 20546.

FOR FURTHER INFORMATION CONTACT:

Mr. Harry Lupuloff, NASA, Director of Patent Licensing, (202) 358-2041.

Dated: January 20, 1995.

Edward A. Frankle,
General Counsel.

[FR Doc. 95-2221 Filed 1-27-95; 8:45 am]

BILLING CODE 7510-01-M

[Notice 95-011]

Intent To Grant an Exclusive Patent License

AGENCY: National Aeronautics and Space Administration.

ACTION: Notice of Intent to Grant a Patent License.

SUMMARY: NASA hereby gives notice of intent to grant On Line, Inc., of Waxhaw, North Carolina, 28173, an exclusive license to practice the invention protected by U.S. Patent Application No. 08/316,708, entitled "MASS DENSITY MEASUREMENT OF A TEXTILE YARN," which was filed on September 29, 1994, by the United States of America as represented by the Administrator of the National Aeronautics and Space Administration. The exclusive license will contain appropriate terms and conditions to be negotiated in accordance with NASA Patent Licensing Regulations (14 CFR part 1245). NASA will negotiate the final terms and conditions and grant the license unless, within 60 days of the date of this notice, the Director of Patent Licensing receives written objections to the grant, together with supporting documentation. The Director of Patent Licensing will review all written responses to this notice and then recommend to the Associate General Counsel (Intellectual Property) whether to grant the license.

DATES: Comments to the Notice must be received by March 31, 1995.

ADDRESSES: National Aeronautics and Space Administration, Code GP, Washington, DC 20546.

FOR FURTHER INFORMATION CONTACT:

Mr. Harry Lupuloff, NASA, Director of Patent Licensing, (202) 358-2041.

Dated: January 20, 1995.

Edward A. Frankle,
General Counsel.

[FR Doc. 95-2222 Filed 1-27-95; 8:45 am]

BILLING CODE 7510-01-M